

COURSE DATA

Data Subject			
Code	44420		
Name	Physical nanomanufacturing techniques		
Cycle	Master's degree		
ECTS Credits	3.0		
Academic year	2023 - 2024		
Study (s)			
Degree		Center	Acad. Period year
2208 - M.D. in Mole Nanotechnology	ecular Nanoscience and	Faculty of Chemistry	1 First term
	ecular Nanoscience and	Faculty of Chemistry	1 First term
Nanotechnology	ecular Nanoscience and	Faculty of Chemistry Subject-matter	1 First term Character
Nanotechnology Subject-matter Degree	ecular Nanoscience and		
Nanotechnology Subject-matter Degree 2208 - M.D. in Mole	1526257	Subject-matter 4 - Physical nanomanufacturing	Character
Nanotechnology Subject-matter Degree 2208 - M.D. in Mole Nanotechnology	1526257	Subject-matter 4 - Physical nanomanufacturing	Character

SUMMARY

The aim is that students learn basic concepts related to nanofabrication based on a bottom-up approach. Particular focus will be devoted to the possibilities and limits of the lithographic techniques, as nanofabrication tools.

PREVIOUS KNOWLEDGE

Relationship to other subjects of the same degree

There are no specified enrollment restrictions with other subjects of the curriculum.



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Other requirements

There are no specified enrollment restrictions with other subjects of the curriculum.

OUTCOMES

2208 - M.D. in Molecular Nanoscience and Nanotechnology

- Students should apply acquired knowledge to solve problems in unfamiliar contexts within their field of study, including multidisciplinary scenarios.
- Students should be able to integrate knowledge and address the complexity of making informed judgments based on incomplete or limited information, including reflections on the social and ethical responsibilities associated with the application of their knowledge and judgments.
- Students should demonstrate self-directed learning skills for continued academic growth.
- Students should possess and understand foundational knowledge that enables original thinking and research in the field.
- To possess the necessary knowledge and abilities to continue with future studies in the PhD program in Nanoscience and Nanotechnology.
- For students from field of knowledge (e.g. chemistry) to be able to scientifically communicate and interact with colleagues from another field (e.g. physics) in the resolution of problems laid out by the Molecular Nanoscience and Nanotechnology.
- To know the methodological approaches used in Nanoscience.
- To know the main techniques for molecular systems nanofabrication.

LEARNING OUTCOMES

The aim is that students acquire basic concepts related to a top-down approximation to nanofabrication. In particular, we will focus on the possibilities and limits of the different available lithographic techniques as tools for nanofabrication.

DESCRIPTION OF CONTENTS

1. M4. Physical nanofabrication techniques.

1) Introduction: Lithographic techniques in the context of nanofabrication techniques.

- 2) Optical lithography
- 2.1. Basic processes and lift-off.
- 2.2. Thin film deposition of resists by spin-coatting.

2.3. Photoresist exposition through a mask: methods and resolution; techniques for resolution improvement; Photoresists: types, examples, evaluation parameters, chemically amplified photoresists.

- 2.4. Holographic lithography
- 2.5. Limits and future of the technique.



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- 3) Etching techniques
- 3.1 Wet etching techniques
- 3.2 Dry etching techniques: reactive ion etching (RIE) and variants, sputtering, laser ablation, etc
- 3.3 Clean rooms.
- 4) Nanolithography by nanoimprinting and microcontact.
- 5.1. Microcontact printing.
- 5.2. Nanoimprint lithography (NIL) and variants: thermal NIL, room temperatura NIL, solvent-assisted
- NIL, step and flash NIL, etc
- 5.3. Molding of plastics: hot embossing, injection, etc..
- 5) Electron beam lithography
- 5.1 The scanning electron microscope
- 5.2 Interactions between electrons and matter
- 5.3 Electron beam lithography: protocols and resolution
- 5.4 Applications and some examples: masks and nanotransistors

6) Focused Ion Beam Lithography and other direct patterning methods

- 6.1 Introduction
- 6.2 FIB methods: sputtering, milling, deposition
- 6.3 Appplications
- 7) Scanning probe lithography
- 7.1 The force microscope
- 7.2 The variety of Scanning probe lithographies
- 7.3 Oxidation SPL
- 7.4 Thermal SPL
- 7.5 Applications: Silicon nanowire transistors; bimolecular sensors; molecular architectures.
- 8) The atomic force microscope in biology and material sciences
- 8.1 Operational principles
- 8.2 AFM modes
- 8.3 Forces and spatial resolution
- 8.4 High resolution imaging of soft matter
- 8.5 Nanomechanical and single molecule force spectroscopies



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WORKLOAD

ACTIVITY	Hours	% To be attended
Theory classes	15,00	100
Tutorials	5,00	100
Seminars	4,00	100
Other activities	2,00	100
Preparation of evaluation activities	39,00	0
Preparing lectures	10,00	0
TOTAL	75,00	

TEACHING METHODOLOGY

- Theory classes, participatory lectures
- Articles discussion.
- Chaired debate or discussion.
- Practical cases or seminar problems discussion.
- Seminars.
- Problems.
- Laboratory practices and demonstracions and visit to installations.
- Experts conferences.
- Attendance to courses, conferences and round tables.

EVALUATION

Written exam about the subject basic contents	70-90%
Attendance and active participation in seminars.	0-10%
Questions answering	10-20%



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REFERENCES

Basic

- - From Instrumentation to Nanotechnology, J.W. Gardner, H.T. Hingle, Gordon & Breach Publishing Group, 1999.

- Micromachines & Nanotechnology: The Amazing New World of the Ultrasmall, David Darling, Silver Burdett Press, 1995.

- Zheng Cui (Author) Micro-Nanofabrication: Technologies and Applications; Higher Education Press; Springer; 2005.

- E. Menard et al. Micro- and Nanopatterning Techniques for Organic Electronic an optoelectronic system; Chem. Rev. 107, 1117, 2007.

- P. Rai-Choudhury (Ed) Handbook of Microlithography, Micromachining and Microfabrication, Vol. 1, SPIE Optical Engineering Press, Bellingham, WA, 1997

- Kazuaki Suzuki & Bruce W. Smith (Eds.)Microlithography: Science & Technology, 2nd Ed. (Optical Sci. and Eng.); CRC Press, 2007

- D. Xia, Z. Ku, S.C. Lee, and S.R.J. Brueck, Nanostructures and Functional Materials Fabricated by Interferometric Lithography, Adv. Mater. 23, 147 179 (2011).

- Evolution in Lithography Techniques: Microlithographyto Nanolithography (Review) Ekta Sharma, Reena Rathi, Jaya Misharwal, Bhavya Sinhmar, Suman Kumari, Jasvir Dalal, and Anand Kumar. Nanomaterials 12, 2754 (2022).

-Fundamentals of microfabrication and nanotechnology. M.J. Madou, CRC Press (2011)

Additional

Amplitude modulation AFM, R. Garcia, Wiley-VCH (2010)

Scanning Probe Microscopy: The lab on a tip, E. Meyer, H. Hug, R. Bennewitz, Springer (2004)

Advanced scanning probe lithography, R. Garcia, A.W. Knoll, E. Riedo, Nature Nanotechnology 9, 577-587 (2014).

Y.F. Dufrêne et al. Imaging modes of atomic force microscopy for application in molecular and cell biology. Nature Nanotechnology 12, 295-307 (2017).

Controlling the emission properties of solution-processed organic distributed feedback lasers through resonator design. V. Bonal, J. A. Quintana, J. M. Villalvilla, P. G. Boj, M. A. D´az-Garc´a; Sci. Rep., 9, 11159 (2019).

N,N´-bis(3-methylphenyl)-N,N´-dyphenylbenzidine based distributed feedback lasers with holographically fabricated polymeric resonators. V. Bonal, J.A. Quintana, J.M. Villalvilla P.G. Boj, R. Muñoz-Mármol, J.C. Mira-Martínez, M.A. Díaz-García; Polymers 13, 3843 (2021).